

Nordic Nanolab User Meeting 7-8 May 2019

Tuesday 7 May

11:00-11:10	Welcome	Plenum: Oticon Hall		Welcome: Jörg Hübner & Flemming Jensen				
11:10-12:00	Invited speaker	Plenum: Oticon Hall		Henri Jansen, DTU Nanolab: Generic build-up of silicon plasma-etch processes				
12:00-13:00	LUNCH	Plenum: Oticon Hall						
	Thematic seminars							
	Analysis/Characterization Room: S010	Chair	Thin Film technologies Room: S01	Chair	Etching technologies Room: S02	Chair	Lithography Room: S04	Chair
13:00-13:50	C1: X-ray Photoelectron Spectroscopy: a powerful characterization tool in material science and biotechnology, Hamid Khanmohammadi, NTNU BASIC	Maria Huffman (Lund)	T1: Thin film deposition tehcniques, Kristin Bergum, Oslo UiO BASIC	Pernille Voss Larsen (DTU)	E1: Generic build-up of etch process: 3D-sculpturing by Si plasma etching, Bingdong Chang, DTU Nanolab ADVANCED	Flemming Jensen (DTU)	L1: EBL hardware basics and craftsmanship, Marcus Rommel, Chalmers BASIC	Thomas Aarøe Anhøj (DTU)
13:50-14:20	Coffee							
14:20-15:10	C2: FT-IR and Raman Spectroscopies: Principles and Applications, Philip M. Weiser, Oslo UiO BASIC	Jesper Hanberg (DTU)	T2: Magnetron sputtering, Tomas Kubart, Uppsala Ångström ADVANCED	Tomas Nyberg (Ångström)	E2: Chemical Mechanical Polishing, Corrado Capriata, KTH BASIC	Karin Hedsten (Chalmers)	L2: Electron beam lithography - process, principles, and capabilities, Jakob Vinje & Einar Digernes, NTNU BASIC	Örjan Vallin (Ångström)
15:10 - 16:30	Meeting Center Foyer			Poster session				
16:45	Bus to hotel							
18:00	DINNER							

Wednesday 8 May

09:00 09:50	Invited speaker	Plenum: Oticon Hall		Per-Erik Hellström, KTH: CMOS processing line for heterogenous integration at KTH				
	Thematic seminars							
	Analysis/Characterization Room: S010	Chair	Thin Film technologies Room: S01	Chair	Etching technologies Room: S02	Chair	Lithography Room: S04	Chair
10:00-10:50	C3: Diffraction Techniques in the Scanning Electron Microscope (SEM), Alice Bastos S. Fanta, DTU Nanolab ADVANCED	Jonas Michael-Lindhard (DTU)	T3: Atomic Layer Deposition (ALD), Pernille V. Larsen & Evgeniy Shkondin, DTU Nanolab BASIC	Mats Hagberg (Chalmers)	E3: Wet etching techniques, Karin Hedsten, Chalmers BASIC	Berit Herstrøm (DTU)	L3: Talbot displacement lithography, Mariusz Graczyk, Lund Nano Lab BASIC	Ivan Maximov (Lund)
10:50-11:10	Coffee							
11:10-12:00	C4: Transmission Electron Microscopy (TEM): Combining analytical methods of imaging, diffraction, and spectroscopy, Lars Riekehr, Uppsala Ångström ADVANCED	Victoria Sternhagen (Ångström)	T4: Epitaxial growth, Matthias Hammar, KTH BASIC	Martin Hollertz (Chalmers)	E4: Atomic Layer Etching, Sabbir Ahmed Khan, KU/NBI BASIC	Örjan Vallin (Ångström)	L4: Block copolymer nanolithography, Anette Löfstrand, Lund Nano Lab BASIC	Mathilde Barriet (NTNU)
12:00-14:00	LUNCH + Lab Tour	Plenum: Oticon Hall		Guided tours around the cleanroom: Remember to sign in				
14:00 -14:50	C5: Intermodulation AFM: material properties at high speed and high resolution, Daniel Forchheimer, KTH ADVANCED	Ken Roger Ervik (NTNU)	T5: From atoms to microfilms: a journey in thin film deposition technology, Ruggero Verre, Chalmers BASIC	Henrik Frederiksen (Chalmers)	E5: Etching AlGaIn alloys using ICP-RIE, Leidulv Vigen, NTNU BASIC	Svenn Ove Linde (NTNU)	L5: Introduction to maskless UV-lithography, Lean Gottlieb Pedersen, DTU Nanolab BASIC	Leif S. Johansen (DTU)
15:00-15:50	Invited speaker	Plenum: Oticon Hall		Heike Riel, IBM Zürich: Nanoelectronic Devices for Future Computing				
15:50	Wrap up							